

## ELEG 646; ELEG 446 - Nanoelectronic Device Principles – Spring 2011

### Homework #12 - due Friday, 13 May 2011, in class

1. Problem 8.5 in chapter 8 of Muller & Kamins, p. 422 in 3rd edition. Hints: start with  $Q_s = -C_{ox}(V_G - V_{FB} - \psi_s)$ , then  $C_G = -dQ_s/dV_G$ . Notes: (a) The symbol  $\phi_s$  in this problem is the same as our  $\psi_s$ , in the class lectures; (b)  $V_{FB}$  is a constant with  $V_G$ , but  $\phi_s$  is not. Recall that  $\psi$  and  $\phi$  differ by a constant. More hints: careful with book's notation: sometimes they use  $\phi_s$  with the meaning as in our lectures, but sometimes they use  $\phi_s$  to mean our  $\psi_s$ , as in Fig. 8.8, and on page 393. See Berglund, IEEE TED, v. ED13, p. 701, 1966.
2. Derive an expression for the depletion width  $x_d$  of an MOS capacitor that is valid for the depletion condition:  $V_{FB} < V_{GS} < V_T$ . Express  $x_d$  in terms of  $V_{GS}$ , and oxide parameters such as  $d_{ox}$ ,  $\epsilon_{ox}$ , etc. The suggested approach is to set up the MOS charging equation:  $V_{ox} + \Psi_s = V_{GS} - V_{FB}$ , where  $V_{ox} = -Q_{dep}/C_{ox}$ , which depends linearly on  $x_d$ , and  $\Psi_s = qN_A x_d^2/2\epsilon_s$ . Solve the resulting quadratic equation for  $x_d$ . Note that this result for  $x_d$  can be used to yield the semiconductor contribution ( $C_s = \epsilon_s/x_d$ ) to the total gate capacitance in this depletion region, by putting  $C_s$  in series with  $C_{ox}$ .
3. Problem 8.6 in chapter 8 of Muller & Kamins, p. 422 in 3rd edition. Hint: Keep in mind that the semiconductor capacitance ( $-Q_G$ ) =  $Q_s = Q_n - qN_A x_d$ , so that  $x_d$  can be expressed in terms of charges.
4. Consider a MOS capacitor of area  $1 \text{ cm}^2$  made on ***n-silicon*** with  $N_D = 1.5 \times 10^{14} \text{ cm}^{-3}$  and an Al gate. The  $\text{SiO}_2$  layer is 200 nm thick. The Si is 20  $\mu\text{m}$  thick and is epitaxially grown on  $n^+$ -silicon substrate having  $N_D = 10^{19} \text{ cm}^{-3}$ . Neglecting any interface charge between Si and  $\text{SiO}_2$ , determine the gate capacitance measured under flat-band conditions. Hint: this is not asking for only the semiconductor depletion capacitance at flat band.
5. Problem 8.14 in chapter 8 of Muller & Kamins, p. 423 in 3rd edition. Hint: consider the motion of ions and the filling of states as the  $V_G$  becomes more positive and then more negative. for both n and p-type substrates.

Homework assignments will appear on the web at:  
<http://www.ece.udel.edu/~kolodzey/courses/eleg646s11.html>

**Include your name, due date, assignment number, and course number on each submission.**